

Substitute Specification

← filed 03/17/2004

Divisional of Application No. 09/946,486

TITLE OF THE INVENTION

**ALIGNMENT METHOD AND EXPOSURE APPARATUS
USING THE METHOD**

This application is a divisional application of copending U.S. patent application
number 09/946,486, filed September 6, 2001.

FIELD OF THE INVENTION

The present invention relates to an alignment method and an exposure apparatus using
the method, and particularly is suitable for an alignment method in semiconductor
manufacturing and method and apparatuses for manufacturing devices using it.

BACKGROUND OF THE INVENTION

Currently, in semiconductor manufacturing, a semiconductor device is fabricated by
depositing multiple layers successively. In actual semiconductor manufacturing, a method is
known wherein instead of measuring positions of alignment marks formed in a layer prior to
exposure, marks are formed in the multiple layers and alignment is performed by measuring
positions of the marks in multiple layers.